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(54) Title: POLISHING COMPOSITION CONTAINING CONDUCTING POLYMER

(57) Abstract: The invention provides a polishing system comprising (a) an abrasive, a polishing pad, a means for oxidizing a substrate, or any combination thereof, (b) a conducting polymer having an electrical conductivity of $10^{-10}$ S/cm to $10^{-6}$ S/cm, and (c) a liquid carrier.

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